

# Generic LibreSilicon process overview

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January 23, 2018

## Abstract

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This is the specification of the free silicon manufacturing standard for manufacturing the ls018<sup>1</sup> standard logic cells and related free technology nodes from the LibreSilicon project.

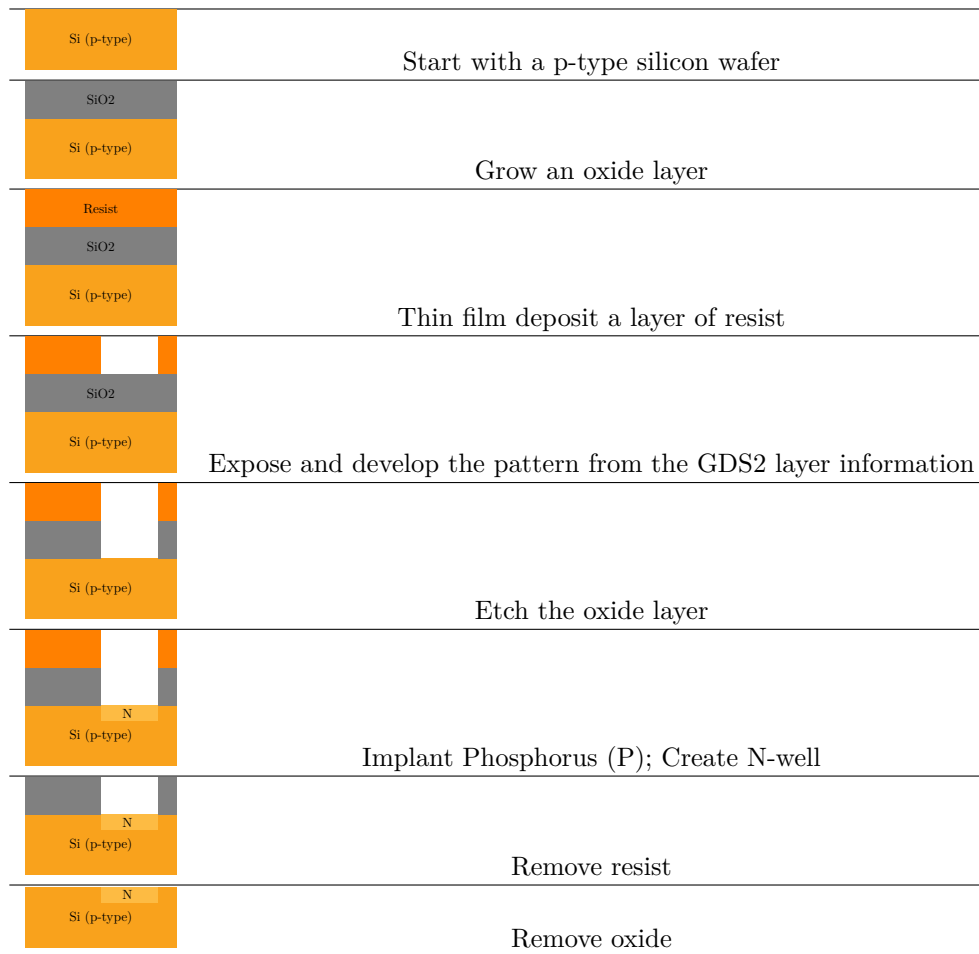
For further clarification consult the complete documentation of the process.

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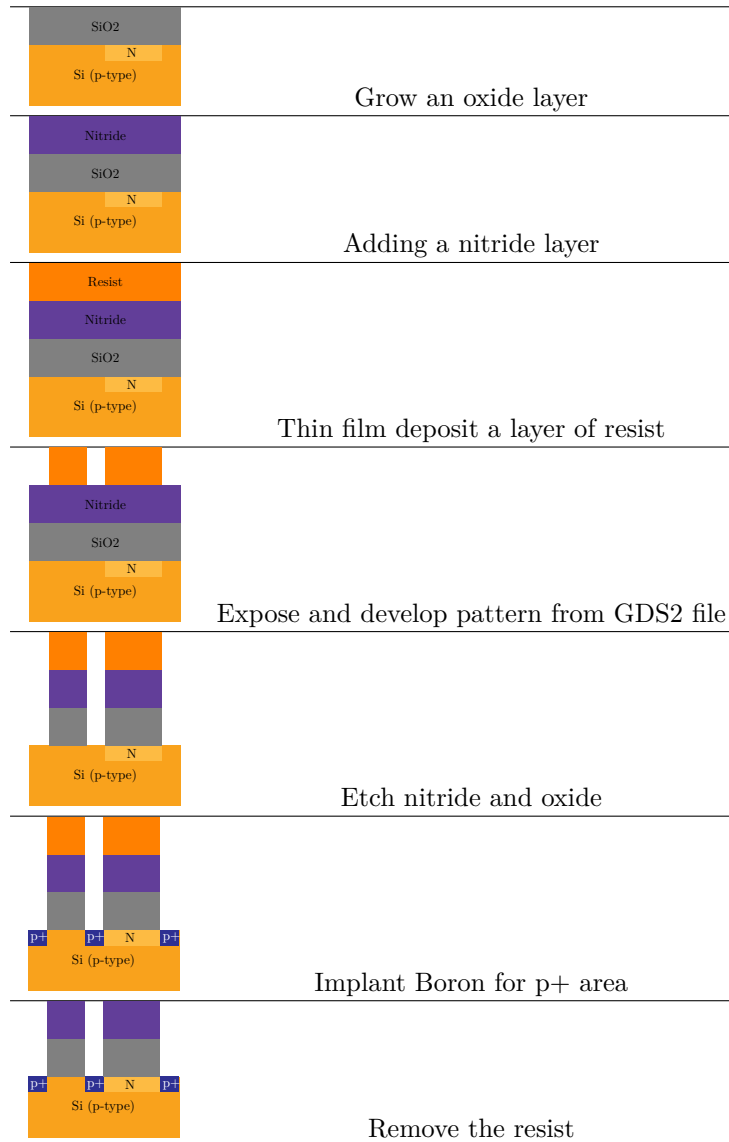
<sup>1</sup><https://github.com/leviathanch/ls018>

# 1 N-Well

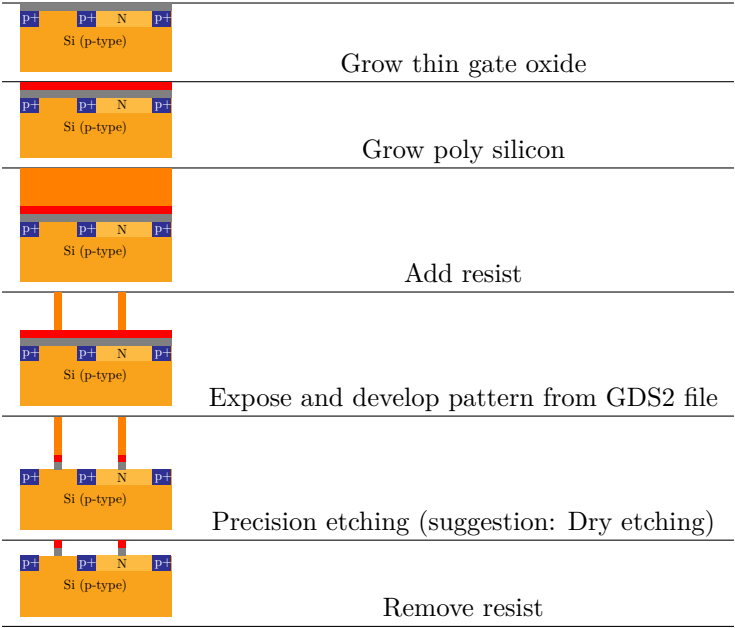
The n-well is required for CMOS technology built on a p-substrate. For this process p-substrate is required.



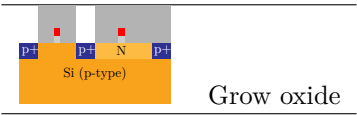
## 2 P+ Implant



### 3 Poly



4 Implant



## 5 Field oxide

